

JPW



PATENT
Customer No. 22,852
Attorney Docket No. 04329.2543-01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Masamitsu ITOH et al.) Group Art Unit: 1752
)
Application No.: 10/665,616) Examiner: Walke, Amanda C.
)
Filed: September 22, 2003)
)
For: PATTERN FORMATION)
MATERIAL, PATTERN)
FORMATION METHOD, AND)
EXPOSURE MASK)
FABRICATION METHOD)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

AMENDMENT

In response to the Office Action dated February 12, 2004, please amend this application as follows:

Amendments to the Claims are reflected in the listing of claims beginning on page 2.

Remarks follow the Amendment section of this paper, beginning on page 5.

Attachments to this amendment include an Appendix consisting of a partial translation of Sato et al. (JP 08-262721); namely paragraph [0007].